

AMENDMENTS TO THE CLAIMS:

Please amend claim 1, as follows:

Claim 1 (currently amended): An electron beam projection mask for ~~arranging use in~~ forming a plurality of high density and low density batch projection regions on a semiconductor substrate so that pattern density may be equalized all over [a] said semiconductor substrate, wherein said high density and low density batch projections are equal in area.

Claim 2 (original): An electron beam projection mask according to claim 1, wherein the mask is a stencil type mask.

Claim 3 (original): An electron beam projection mask according to claim 1, wherein the mask is a membrane type mask.

Claim 4 (original): An electron beam projection mask according to claim 1, wherein the mask is a partial batch electron beam projection mask.

Claim 5 (original): An electron beam projection mask according to claim 2, wherein the mask is a partial batch electron beam projection mask.

Claim 6 (original): An electron beam projection mask according to claim 3, wherein the mask is a partial batch electron beam projection mask.

Claim 7 (original): An electron beam projection mask as claimed in claim 1, wherein the mask is an electron beam projection lithography mask.

Claim 8 (original): An electron beam projection mask as claimed in claim 2, wherein the mask is an electron beam projection lithography mask.

Claim 9 (original): An electron beam projection mask as claimed in claim 3, wherein the mask is an electron beam projection lithography mask.

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